

<b>Notice of References Cited</b>		Application/Control No.	Applicant(s)/Patent Under Reexamination ENDO ET AL.	
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		Kathleen Duda	1756	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

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